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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 8728**
Norio KIMURA et al. : Attorney Docket No. 2000_1761A
Serial No. 09/742,386 : Group Art Unit 1763
Filed December 22, 2000 : Examiner Karla A. Moore
APPARATUS AND METHOD FOR :
PROCESSING SEMICONDUCTOR
SUBSTRATE

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is in response to the Restriction Requirement of March 22, 2007.

Applicants, by their undersigned representative, hereby elect the invention of Group II directed to claims 110-113 and 115-117.

Having made the required election, a full examination on the merits of the elected invention is hereby requested.

Respectfully submitted,

Norio KIMURA et al.

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